



IFW

**PATENT APPLICATION**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Tae Wan LEE et al.

Group Art Unit: 1722

Application No.: 10/724,187

Examiner: F. Hiteshew

Filed: December 1, 2003

Docket No.: 117904

For: METHOD FOR FORMING SILICON EPITAXIAL LAYER

**AMENDMENT UNDER 37 C.F.R. §1.111**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In reply to the April 4, 2005 Office Action, please consider the following:

**Amendments to the Claims** as reflected in the listing of claims; and

**Remarks.**